

ALUMINUM ZINC OXIDE LAYERS BY HIGH-PRESSURE SPUTTERING FOR SOLAR CELLS APPLICATION.

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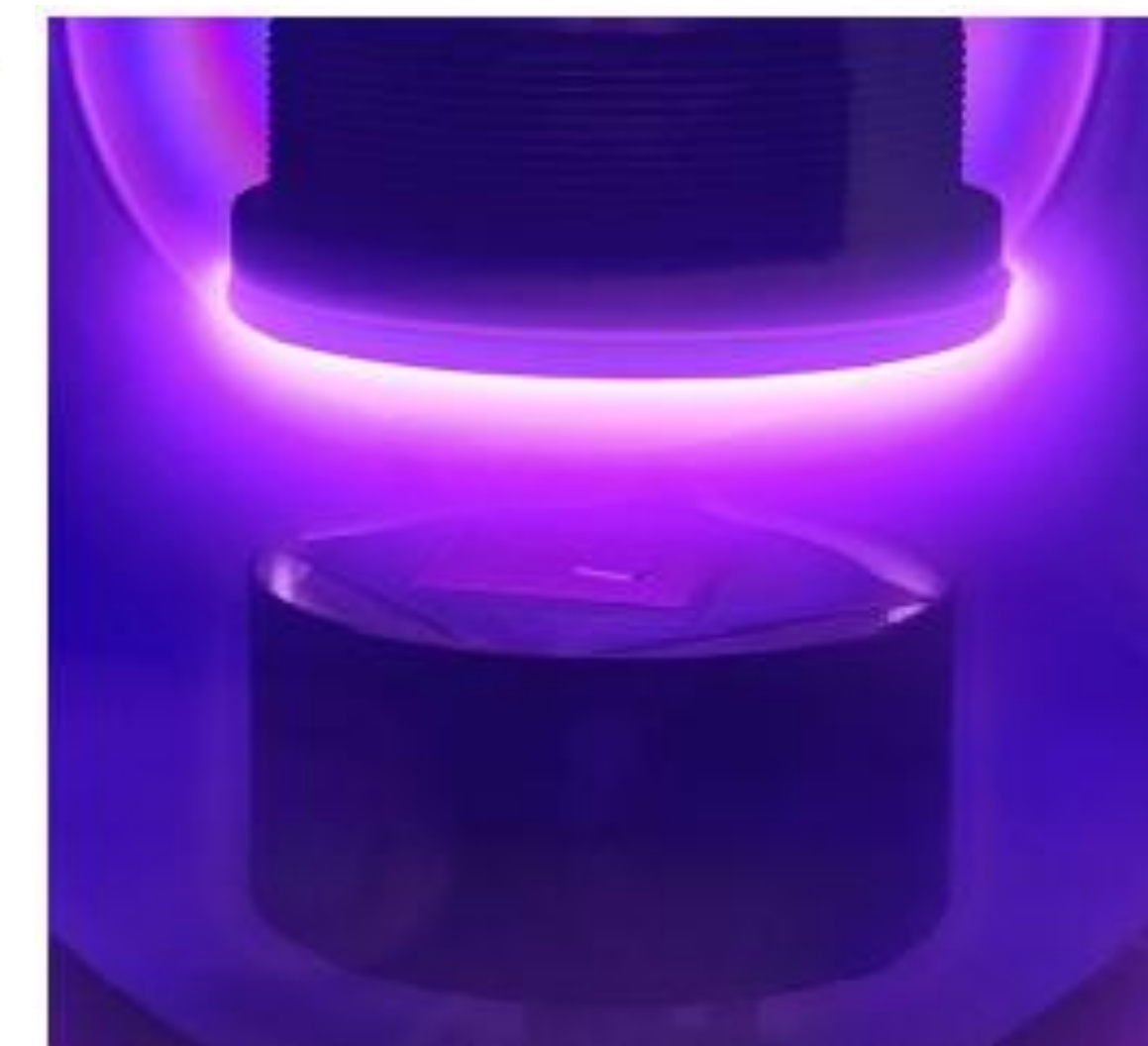
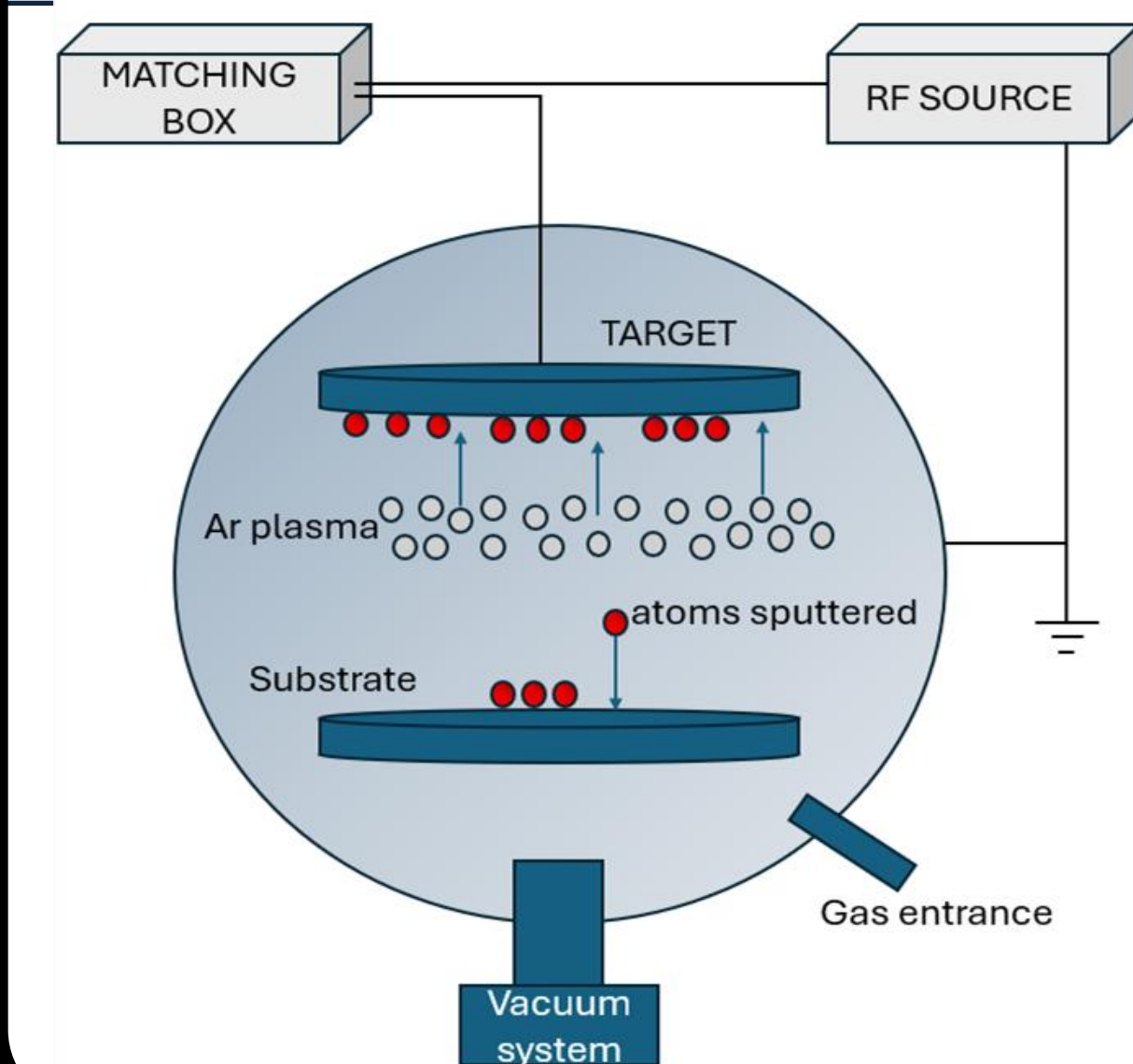
MOTIVATION

- ITO limitations:** High cost and scarcity of indium restrict large-scale use of ITO in transparent electrodes.
- AZO advantages:** Aluminum-doped ZnO is abundant, low-cost, non-toxic, highly transparent, and combines good conductivity with stability.
- Common AZO deposition methods:** low-pressure magnetron sputtering, Pulsed Laser Deposition (PLD), or Chemical Vapor Deposition (CVD).
- High-pressure sputtering (HPS):** At mbar pressures, thermalized species reduce substrate damage and enable dense, conductive films even at low substrate temperatures.

$$\lambda = \frac{kT}{\sqrt{2\pi}d^2p}$$

EXPERIMENTAL

- Sputtering pressure: **0.46-2.2 mbar**
- Power: **100W, AZO target (ZnO/Al₂O₃), x6 Ar atmosphere**

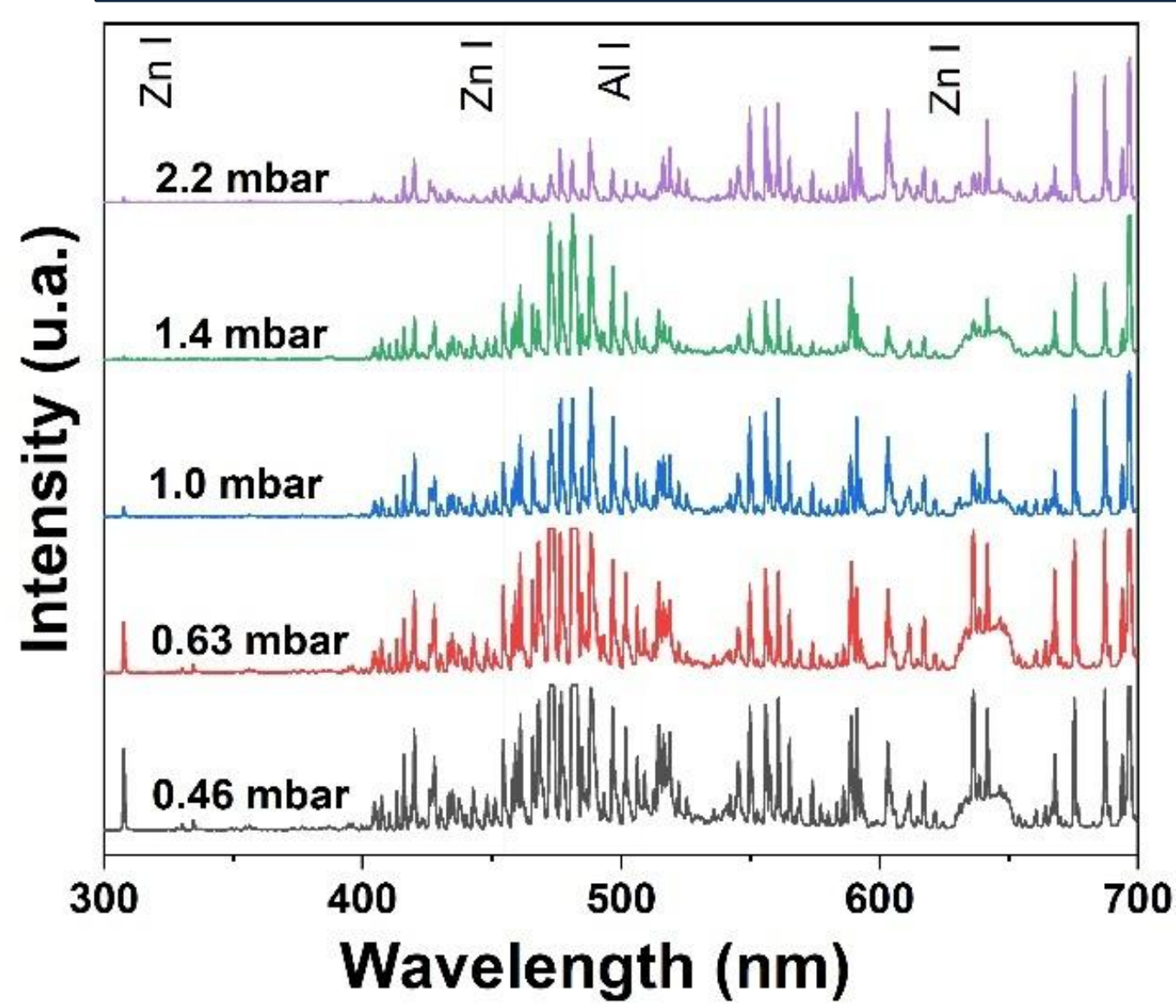


Characterization techniques

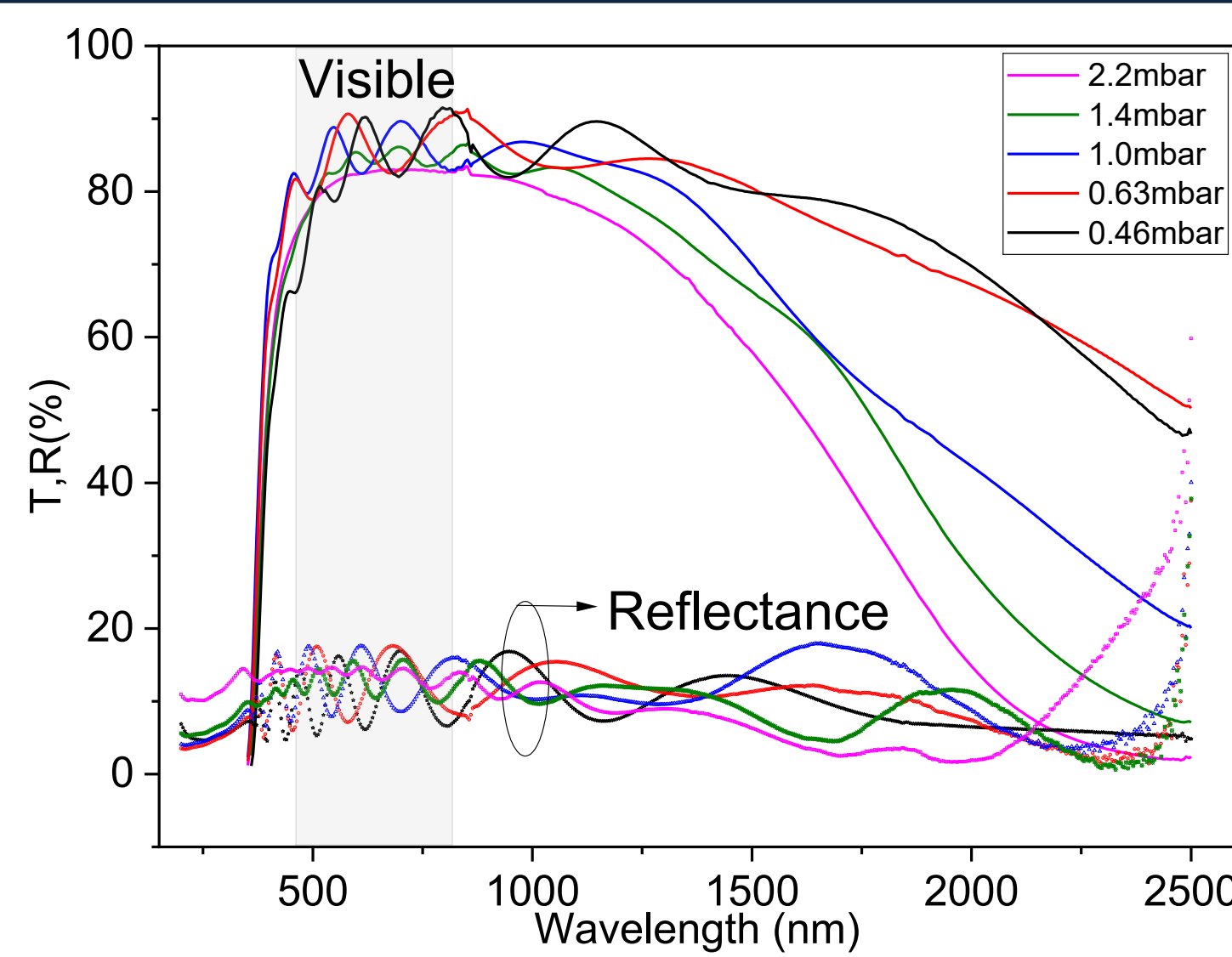
- OES ✓
- Ellipsometry ✓
- Transmittance ✓
- Reflectance ✓
- XPS ✓
- GIXRD ✓
- AFM ✓
- Resistivity ✓
- Carrier concentration ✓
- Mobility ✓

RESULTS

OPTICAL EMISSION SPECTROMETRY

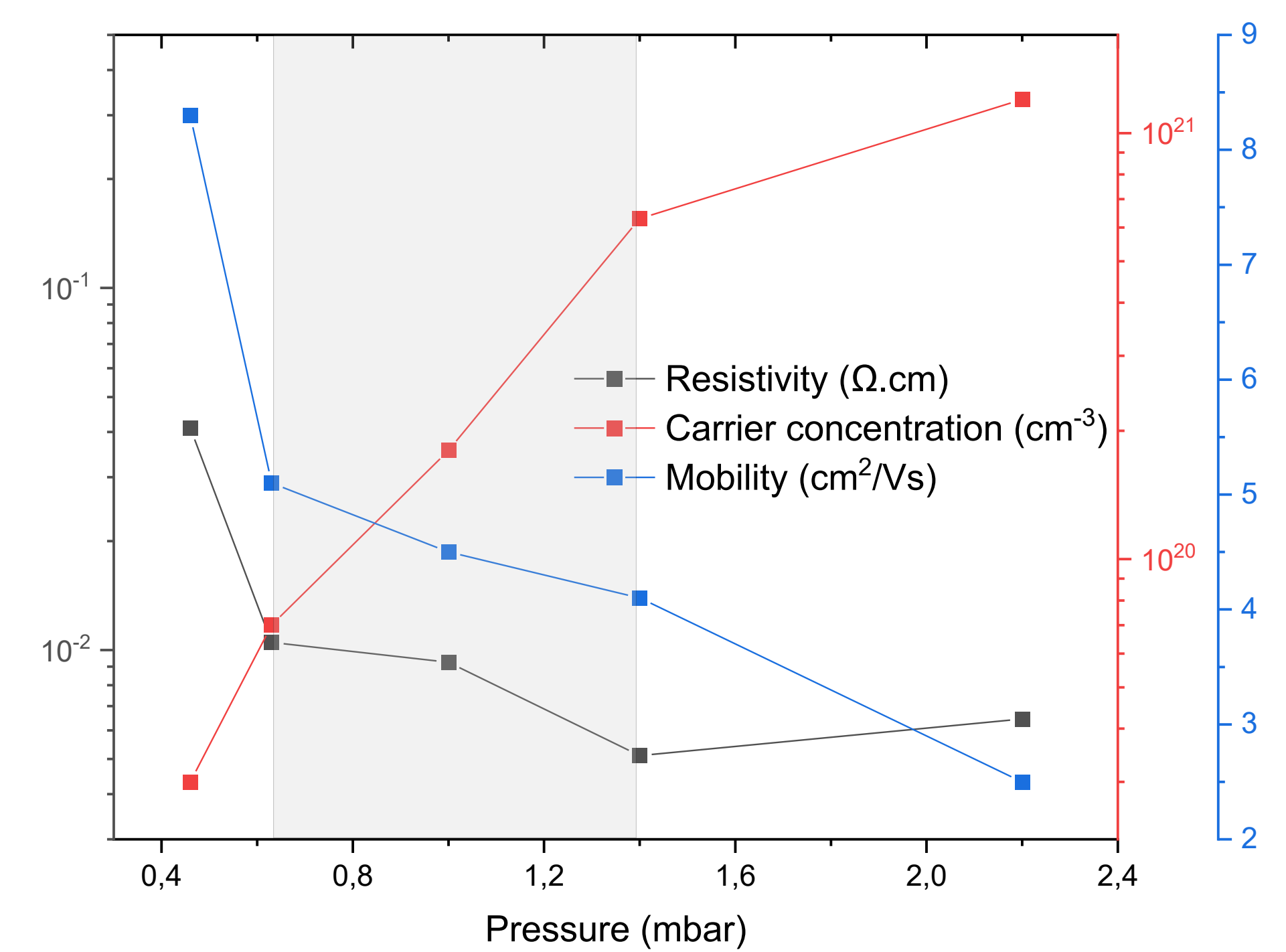


TRANSMITTANCE & REFLECTANCE



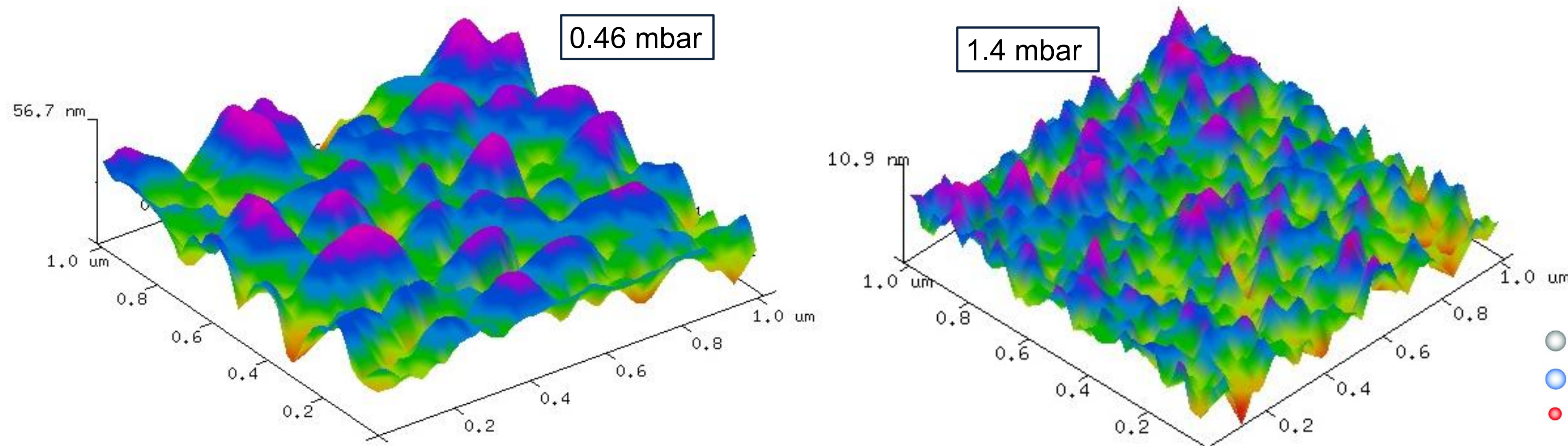
- Average T: **~80–83%, stable across pressures.**
- Low, smooth R(λ) and high flat T(λ) indicate limited light scattering, **consistent with a dense, low-roughness AZO film** suitable for TCO use.

ELECTRICAL CHARACTERIZATION



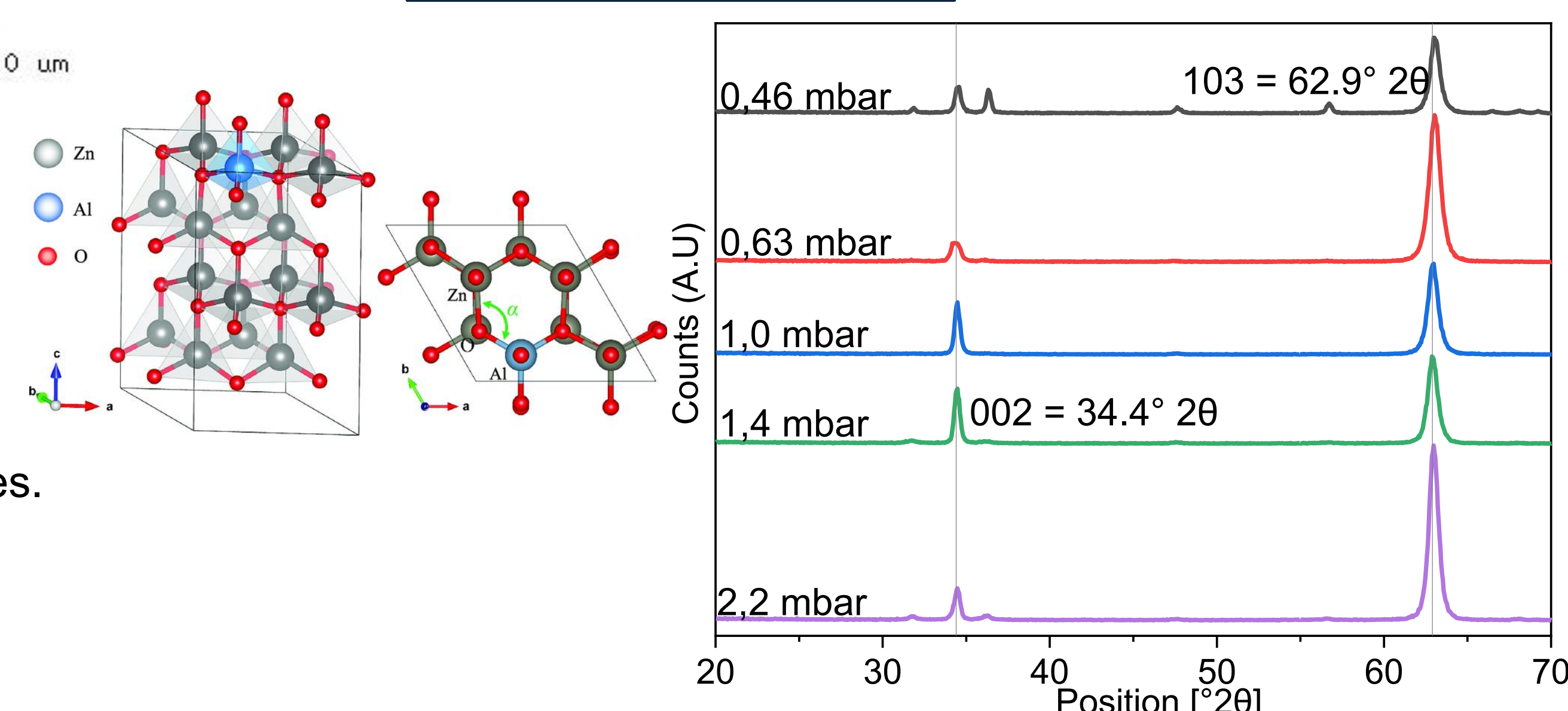
- Carrier concentration **increases with pressure**, leading to higher conductivity. Increased collisions between carriers, **decreasing mobility (μ).**
- Higher pressures promote the formation of more defects in the film, leading to a **decrease in carrier mobility**

ATOMIC FORCE MICROSCOPY



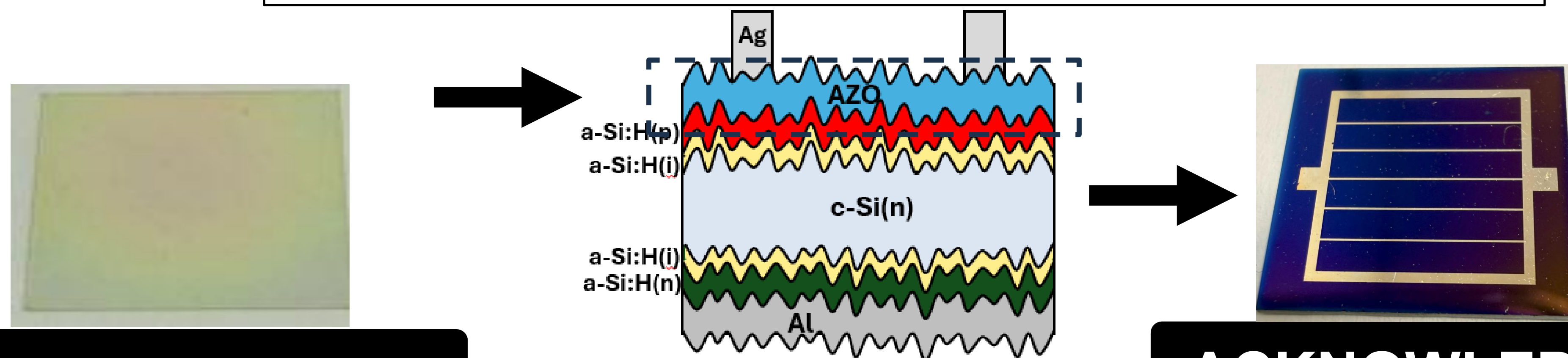
- Roughness decreases from 0.46 → 1.0–1.4 mbar, yielding more uniform, high-quality films.
- Optimal window: 1.0–1.4 mbar (smooth, dense morphology; controlled growth).
- *At 2.2 mbar the roughness increases → deposition becomes less controlled, not ideal for smooth surfaces.

X-RAY DIFFRACTION



- Wurtzite ZnO with dominant (002) at 34.4°; (103) at 62.9° is also present.
- Coincidence of the peaks with the expected positions corresponds to the **hexagonal wurtzite phase**, typical of AZO
- (002) texture strengthens around 0.63–1.0 mbar, indicating better c-axis orientation.

FROM AZO FILM TO SOLAR CELL: DEPOSITION, INTEGRATION, DEVICE



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CONCLUSIONS

- We have deposited AZO using High-Pressure Sputtering (HPS), and the resulting films are **suitable for use in solar cells.**
- In the pressure range of **0.63 mbar to 1 mbar**, the films produced show a favorable balance between low resistivity, high transmittance, adequate roughness and optimal AZO properties.

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